

CLATMS:

1. A silicon oxide powder represented by the formula:
Si_xO wherein x is from 1.05 to 1.5 and having a BET specific
5 surface area of 5 to 300 m²/g.
2. A method for preparing the silicon oxide powder of
claim 1, comprising the steps of:
 - heating a raw material powder mixture containing at
10 least a silicon dioxide powder in an inert gas atmosphere or
in vacuum at a temperature of 1,100 to 1,600°C to generate
SiO gas,
 - continuously or intermittently feeding oxygen gas to
the SiO gas to form a gas mixture, and
 - 15 depositing the gas mixture on a surface of a cooled
substrate.
3. The method of claim 2 wherein the depositing step
includes cooling the substrate surface at a temperature of
20 200 to 400°C.